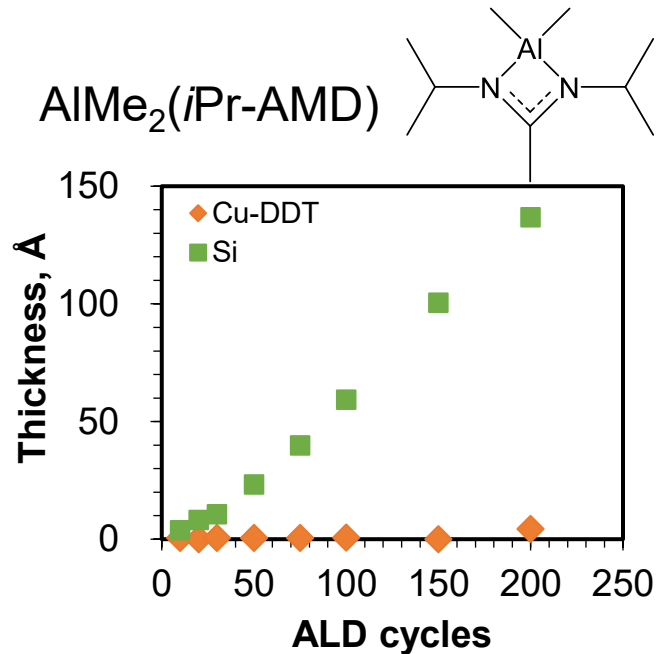
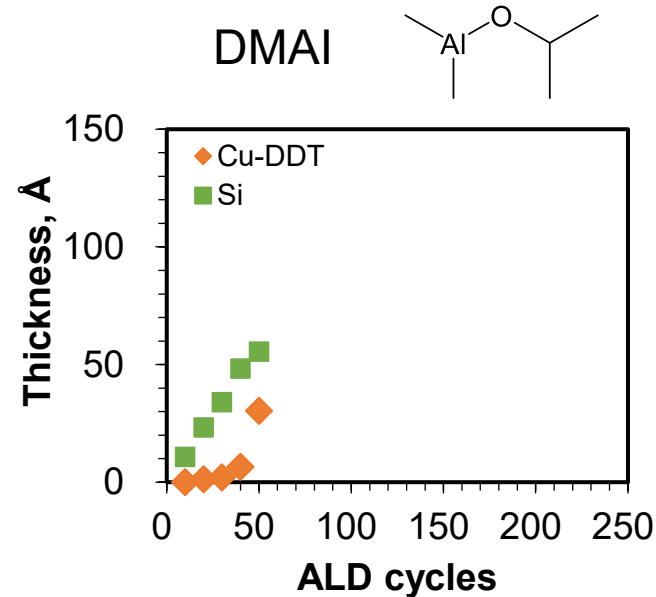


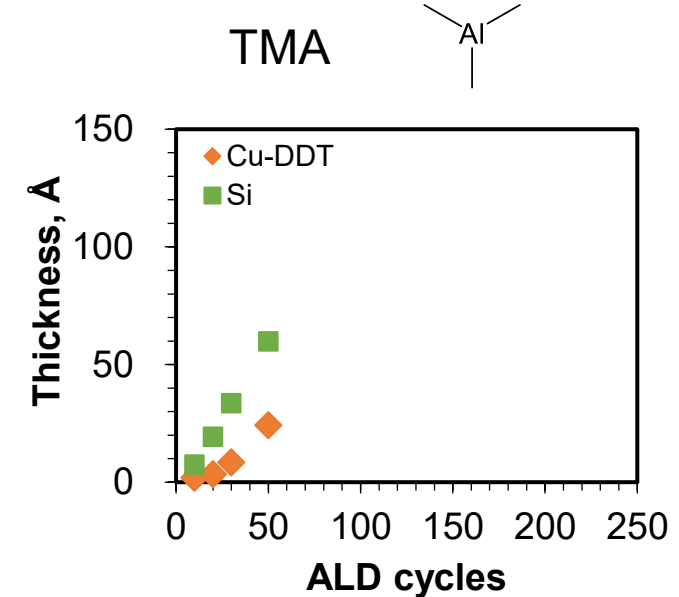
Deposition temperature: 150 °C, Co-reactant: H₂O, Substrates: DDT passivated Cu, native oxide Si



Selective loss ~200 cycles
Selectivity >100 Å



Selective loss ~40 cycles
Selectivity >30 Å



Selective loss ~10 cycles
Selectivity >10 Å

➤ $\text{AlMe}_2(\text{iPr-AMD})$ shows excellent selectivity compared to DMAI and TMA.